

REMARKS/ARGUMENTS

Claims 1-19 are active in the case.

The Examiner's indication of the allowance of Claims 17-19 and the indication of allowable subject matter in Claims 3, 6, 8 and 14-16 is appreciated.

The specification has been amended on page 26 to insert the appropriate Greek letters in positions now occupied by a box symbol. Evidence for the fact that these were typographical errors is found in paragraphs [0037] and [0038] of JP 2002-285342, which is the patent publication of Japanese Patent Application 2001-092715, filed March 28, 2001 and incorporated by reference on page 1 of the present specification. For the Examiner's convenience a red arrow marks the lines which show the proper Greek letters in the patent publication.

The rejection of Claims 1, 2, 4, 5, 7 and 9-13 under 35 U.S.C. §102(e) as anticipated by Hiraoka et al is traversed.

The method of Claims 1 and 2 of the present invention comprises forming on the surface of an insulating body a photosensitive layer containing both a photosensitive compound forming an ion-exchange group or causing an ion-exchange group to disappear upon irradiation with an energy beam and a cross-linkable compound having a cross-linkable group. Hiraoka et al merely shows a porous body impregnated with a photosensitive composition like that shown in Examples 1 and 2 of Hiraoka et al. Therefore, since the photosensitive composition of Hiraoka et al is not formed on the surface of an insulating body, Claims 1 and 2 are not anticipated by Hiraoka et al.

Claims 4 and 5 of the present invention comprise forming on a surface of an insulating body a photosensitive layer containing a photosensitive polymer having both a photosensitive group capable of forming an ion-exchange group or causing an ion-exchange group to disappear upon irradiation with an energy beam and a cross-linkable group.

Hiraoka et al does not teach or suggest a photosensitive polymer having both a photosensitive group capable of forming an ion-exchange group or causing an ion-exchange group to disappear upon irradiation with an energy beam and a cross-linkable group and does not form the photosensitive polymer on the surface of an insulating body, therefore, Claims 4 and 5 are not anticipated by Hiraoka et al.

Claim 7 of the present invention describes a photosensitive composition which comprises a polymer having a photosensitive group forming an ion-exchange group upon irradiation with an energy beam and a cross-linkable group capable of a radical polymerization. Hiraoka et al does not teach or suggest a polymer having a photosensitive group forming an ion-exchange group upon irradiation with an energy beam and a cross-linkable group capable of a radical polymerization and, therefore, Claim 7 is not anticipated by Hiraoka et al.

Claim 9 of the present invention recites a photosensitive layer containing a composition having both photosensitive compound capable of forming an ion-exchange group or causing an ion-exchange group to disappear upon irradiation with an energy beam and a cross-linkable compound, or containing a photosensitive polymer having both photosensitive group capable of forming an ion-exchange group or causing an ion-exchange group to disappear upon irradiation with an energy beam and a cross-linkable group. Hiraoka et al merely describes a three-dimensional structure comprising a porous body and a plurality of regions having a photosensitive composition loaded in the porous body and does not describe a composition with the properties described above. Claim 9 is not anticipated by Hiraoka et al.

Claim 10 recites a photosensitive layer which contains a polymer having a photosensitive group capable of generating an ion-exchange group upon irradiation with an energy beam and a radical polymerizable group, and a radical generating agent. Hiraoka et al

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does not teach or suggest a polymer having a photosensitive group capable of generating an ion-exchange group upon irradiation with an energy beam and a radical polymerizable group, and a radical generating agent, and, therefore, Claim 10 is not anticipated by Hiraoka et al.

Claims 11-13 recite that the compound forming an ion-exchange group in the presence of the acid is a copolymer having a first repeating unit having ion-exchange groups and a second repeating unit having an atomic group not decomposed by an acid and insoluble in an alkali, and some or all of said ion-exchange groups are protected by a protective group. Hiraoka et al does not teach or suggest a compound forming an ion-exchange group in the presence of the acid is a copolymer having a first repeating unit having ion-exchange groups and a second repeating unit having an atomic group not decomposed by an acid and insoluble in an alkali, and some or all of said ion exchange groups are protected by a protective group, and, therefore, Claims 11-13 are not anticipated by Hiraoka et al.

It is submitted that Claims 1-19 are allowable and such action is respectfully requested.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND,  
MAIER & NEUSTADT, P.C.  
Norman F. Oblon



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Roland E. Martin  
Registration No.: 48,082

Customer Number  
**22850**

Tel: (703) 413-3000  
Fax: (703) 413 -2220  
(OSMMN 06/04)  
REM:smi